

FORM PTO-1449

7059

Docket Number (Optional)  
5684/CPI/COPPERApplication Number  
10/074,855

# INFORMATION DISCLOSURE CITATION P E

## IN AN APPLICATION

(Use several sheets if necessary)

MAR 25 2002

Applicant  
PERRINFiling Date  
February 11, 2002

Group Art Unit

### U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>pm</i>	4	1	1	6	7	9	1	9/26/78	Zega	427	524	
	4	7	7	4	4	3	7	9/27/88	Helmer, et al.	315	111.81	
	4	8	6	5	7	1	2	9/12/89	Mintz	204	299.16	
	4	9	6	0	7	5	3	10/2/90	Collins, et al.	204	299.06	
	5	1	5	8	6	6	0	10/27/92	Devigne, et al.	204	299.21	
	5	1	7	8	7	3	9	1/12/93	Barnes, et al.	204	192.51	
	5	2	8	8	9	7	1	2/22/94	Knipp	219	192.51	
	5	5	0	5	7	8	0	4/9/96	Dalvie, et al.	116C	723MA	
	5	6	8	1	4	3	4	10/28/97	Eastlund	204	156.00	
	5	7	7	2	7	7	2	6/30/98	Chi	119	723MA	
	6	0	7	7	4	0	6	6/20/00	Kawakubo, et al.	204	299.12	
	6	1	5	0	6	2	8	11/21/00	Smith, et al.	219	121.54	
<i>pm</i>	6	2	5	1	2	4	2	6/26/01	Fu, et al.	204	299.19	

### FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	Translation	
												YES	NO
<i>pm</i>	9	9	0	0	8	2	3	1/7/99	PCT	<del>_____</del>	<del>_____</del>	full	
<i>pm</i>	61	2	8	4	5	7	3	12/15/86	JP	<del>_____</del>	<del>_____</del>	abstract	

### OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>pm</i>	Chapman, Brian. "Glow Discharge Processes: Sputtering & Plasma Etching," John Wiley & Sons, NY, 1980: pp. 257-258.
	Kitamoto, Y., et al. "Compact Sputtering Apparatus for Depositing Co-Cr Alloy Thin Films in Magnetic Disks," Proc. of the 4 <sup>th</sup> ISSP, Japan, 1997: pp. 519 - 522.
	Musil, J., et al. "Unbalanced Magnetrons and New Sputtering Systems with Enhanced Plasma Ionization," J. Vac. Sci. Tech., A 9 (3), May/June 1991: pp. 1171 - 1177.
<i>pm</i>	Yamazato, M., et al. "Preparation of TiN Thin Films by Facing Targets Magnetron Sputtering," Proc. of the 4 <sup>th</sup> ISSP, Japan, 1997: pp. 635 - 638.

EXAMINER

DATE CONSIDERED

10/6/03

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.